

The structure and composition of rf reactively sputtered

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Citation Report

#	ARTICLE	IF	CITATIONS
1	Preparation and compositional analysis of sputtered TaN films. Journal of Applied Physics, 1978, 49, 5284-5287.	2.5	20
2	Insulating films. , 1978, , .		0
3	Friction properties of sputtered dichalcogenide layers. Tribology International, 1981, 14, 329-332.	5.9	45
4	Stoichiometry and friction properties of sputtered MoSx layers. Thin Solid Films, 1985, 129, 79-91.	1.8	110
5	Correlation between process conditions, chemical composition and morphology of MoS2 films prepared by RF planar magnetron sputtering. Journal Physics D: Applied Physics, 1986, 19, 1575-1585.	2.8	48
6	Effect of deposition variables on the properties of molybdenum sulfide films prepared by the activated reactive evaporation technique. Surface and Coatings Technology, 1989, 39-40, 683-690.	4.8	7
7	Cathodic sputtering for preparation of lubrication films. Surface and Coatings Technology, 1990, 43-44, 629-639.	4.8	24
8	Preparation and properties of MoSx films grown by d.c. magnetron sputtering. Surface and Coatings Technology, 1990, 41, 127-134.	4.8	57
9	The preparation of thin films by physical vapour deposition methods. Thin Solid Films, 1990, 191, 91-126.	1.8	231
10	MoS _{2-x} O _x solid solutions in thin films produced by rf-sputter-deposition. Journal of Materials Research, 1990, 5, 218-222.	2.6	79
11	Novel chemical preparative route for semiconducting MoSe2 thin films. Journal of Materials Chemistry, 1991, 1, 301.	6.7	13
12	A New Chemical Method of Preparing Semiconducting MoX2(X=S, Se) Thin Films. Japanese Journal of Applied Physics, 1991, 30, 3484-3487.	1.5	7
13	Plasma reaction of group VI metal carbonyls. Plasma Chemistry and Plasma Processing, 1992, 12, 147-159.	2.4	12
14	Reactive sputtering of molybdenum sulfide thin films. Surface and Coatings Technology, 1994, 68-69, 422-426.	4.8	6
15	Electrochemical deposition of MoS2 thin films by reduction of tetrathiomolybdate. Thin Solid Films, 1996, 280, 86-89.	1.8	134
16	Title is missing!. Journal of Materials Science Letters, 2000, 19, 803-804.	0.5	24
17	Ion-assisted deposition of MoSx films from laser-generated plume under pulsed electric field. Journal of Applied Physics, 2001, 89, 1449-1457.	2.5	49
18	Chemical synthesis and compositional analysis of mixed [Mo(S _{1-x}) ₂]ETQq1 1 0.784314 rgBT /Overlock 10 Tf 50 67 Td (x</sub>S	3.7	12

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19	Reactive magnetron sputtering of molybdenum sulfide thin films: In situ synchrotron x-ray diffraction and transmission electron microscopy study. <i>Journal of Applied Physics</i> , 2004, 95, 7665-7673.	2.5	19
20	Structural modification and tribological behavior improvement of solid lubricating WSe ₂ coatings during pulsed laser deposition in buffer He-Gas. <i>Journal of Friction and Wear</i> , 2013, 34, 262-269.	0.5	3
21	Tribological properties of gradient MoSe ₂ /Ni ₃ C thin films obtained by pulsed laser deposition in standard and shadow mask configurations. <i>Thin Solid Films</i> , 2014, 556, 35-43.	1.8	23
22	The p-type MoS ₂ nanocube modified poly(diallyl dimethyl ammonium chloride)-mesoporous carbon composites as a catalytic amplification platform for electrochemical detection of l-cysteine. <i>Sensors and Actuators B: Chemical</i> , 2015, 221, 1162-1169.	7.8	32
23	Synthesis, characterization, and tribological evaluation of HPPMS (Cr _{1-x} Al _x)N + MoS ₂ coatings. <i>Surface and Coatings Technology</i> , 2016, 308, 383-393.	4.8	18
24	Temperature controlled 1T/2H phase ratio modulation in mono- and a few layered MoS ₂ films. <i>Applied Surface Science</i> , 2019, 479, 1236-1245.	6.1	29
25	One-step H ₂ S reactive sputtering for 2D MoS ₂ /Si heterojunction photodetector. <i>Nanotechnology</i> , 2020, 31, 225205.	2.6	9
26	Defects induced photoluminescence and ellipsometric measurements of reactive sputtered growth MoS ₂ nanoworms. <i>Optical Materials</i> , 2021, 113, 110848.	3.6	5
27	Self-Lubricating Composites for Extreme Environmental Conditions. <i>Composite Materials Series</i> , 1986, 1, 397-447.	0.2	18
28	Sputtertechniken. <i>WFT Werkstoff-Forschung Und -Technik</i> , 1987, , 95-120.	0.2	0
29	CATHODIC SPUTTERING FOR PREPARATION OF LUBRICATION FILMS. , 1990, , 629-639.		0
30	CVD Processes to Enhance Corrosion and Wear Protection. , 1997, , 49-75.		0
31	Reibungsarme und verschleißfeste Schichten. , 1983, , 135-206.		0